

# **IPC313N10N3R**

# **OptiMOS**<sup>™</sup>3 Power MOS Transistor Chip

Туре	V <sub>(BR)DSS</sub>	R <sub>DS(on)</sub>	Die size	Thickness
IPC313N10N3R	100 V	$2.7~\text{m}\Omega^{1)}$	6 * 5.2 mm <sup>2</sup>	220 μm

## **DESCRIPTION**

- N-channel enhancement mode
- For dynamic characterization refer to the datasheet of IPB027N10N3 G<sup>2)</sup>
- AQL 0.65 for visual inspection according to failure catalogue
- Electrostatic Discharge Sensitive Device according to JEDEC
- Die bond: soldered or glued
- Backside metallization: NiV system
- Frontside metallization: AlCu system
- Passivation: nitride (only on edge structure)

## Electrical Characteristics on Wafer Level

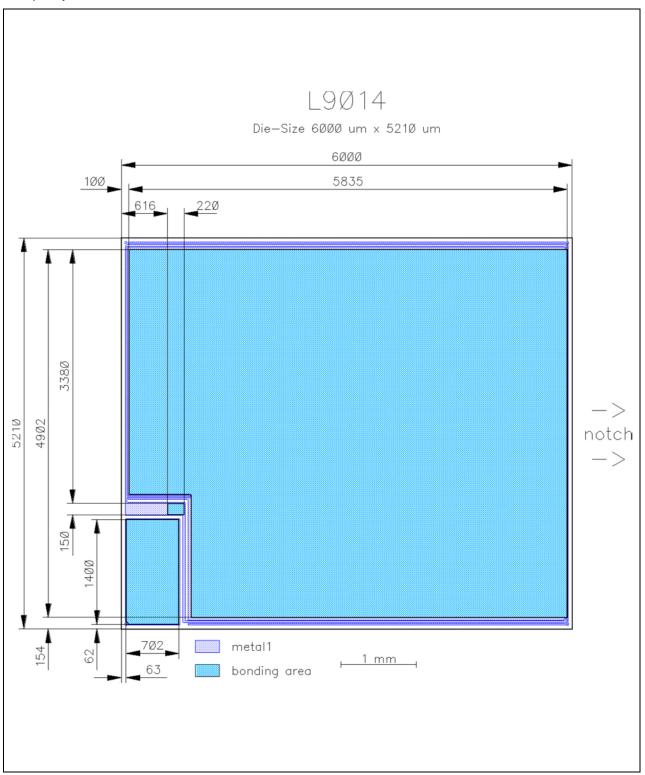
at  $T_j = 25$  °C, unless otherwise specified.

Parameter	Symbol	Value			Unit	Conditions
		min.	typ.	max.		
Drain-source breakdown voltage	V <sub>(BR)DSS</sub>	100	-	-	V	V <sub>GS</sub> = 0V
						$I_D = 1 \text{ mA}$
Gate threshold voltage	V <sub>GS(th)</sub>	2	2.7	3.5	V	$V_{DS} = V_{GS}$
						I <sub>D</sub> = 275 μA
Zero gate voltage drain current	<i>I</i> DSS	-	0.1	1	μΑ	$V_{GS} = 0V$
						V <sub>DS</sub> = 100 V
Gate-source leakage current	I <sub>GSS</sub>	-	1	100	nA	V <sub>GS</sub> = 20 V
						$V_{DS} = 0 V$
Drain-source on-resistance	$R_{\rm DS(on)}$	-	1.9 <sup>3)</sup>	100 4)	mΩ	V <sub>GS</sub> = 10 V
						I <sub>D</sub> = 2.0 A
Reverse diode forward on-voltage	<b>V</b> SD	-	1.0	1.2	V	V <sub>GS</sub> =0 V
						I <sub>F</sub> = 1 A
Internal gate resistance	R <sub>G</sub>	-	8	-	Ω	
Avalanche energy, single pulse	E <sub>AS</sub>	-	45 <sup>5)</sup>	-	mJ	$I_D=30 \text{ A}, R_{GS}=25 \Omega$



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Chip-Layout:



<sup>1)</sup> packaged in a P-TO263-3 (see ref. product)

 $<sup>^{2)}</sup>$  IPB027N10N3 G dynamic characterization does not include the internal added  $R_{\text{\scriptsize G}}$ 

 $<sup>^{3)}\,</sup>typical$  bare die  $R_{DS(on)};\,V_{GS}\!\!=\!\!10V$ 

<sup>4)</sup> limited by wafer test-equipment

<sup>&</sup>lt;sup>5)</sup> Wafer tested. For general avalanche capability refer to the datasheet of IPB027N10N3 G



## **IPC313N10N3R**

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